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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q78231

Henning SIRRINGHAUS

Appln. No.: 10/693,100

Group Art Unit: 1765

Confirmation No.: 8457

Examiner: not yet assigned

Filed: October 27, 2003

For: DOPING OF SOURCE-DRAIN CONTACTS

SUBMISSION OF PRIORITY DOCUMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Submitted herewith is one (1) certified copy of the priority document on which a claim to priority was made under 35 U.S.C. § 119. The Examiner is respectfully requested to acknowledge receipt of said priority document.

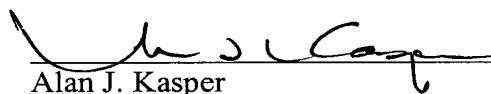
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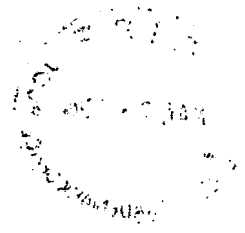
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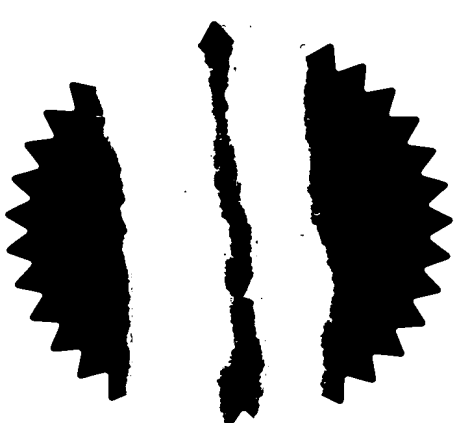
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3. Full name, address and postcode of the or of each applicant (underline all surnames)

08184533001

Patents ADP number (if you know it)

If the applicant is a corporate body, give the country/state of its incorporation

Plastic Logic Ltd.
34 Cambridge Science Park
Milton Rd.
Cambridge CB4 0FX

4. Title of the invention

Self-aligned doping of source-drain contacts

5. Name of your agent (if you have one)

"Address for service" in the United Kingdom to which all correspondence should be sent (including the postcode)

00001255003

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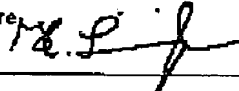
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Self-aligned doping of source-drain contacts

This invention relates to solution processed devices and methods for forming such devices.

Semiconducting conjugated polymer thin-film transistors (TFTs) have recently become of interest for applications in cheap, logic circuits integrated on plastic substrates (C. Drury, et al., APL 73, 108 (1998)) and optoelectronic integrated devices and pixel transistor switches in high-resolution active-matrix displays (H. Sirringhaus, et al., Science 280, 1741 (1998), A. Dodabalapur, et al. Appl. Phys. Lett. 73, 142 (1998)). In test device configurations with a polymer semiconductor and inorganic metal electrodes and gate dielectric layers high-performance TFTs have been demonstrated. Charge carrier mobilities up to $0.1 \text{ cm}^2/\text{Vs}$ and ON-OFF current ratios of 10^6 - 10^8 have been reached, which is comparable to the performance of amorphous silicon TFTs (H. Sirringhaus, et al., Advances In Solid State Physics 39, 101 (1999)).

In PCT/GB00/04934 techniques are disclosed that allow fabrication of polymer TFTs by a combination of direct printing and solution processing. These manufacturing techniques are inherently lower cost than inorganic semiconductor manufacturing techniques based on vacuum deposition and photolithographic patterning, and are well suited for fabrication of low cost electronic circuits on large areas and flexible substrates.

One of the key factors that determines the performance of a polymer TFT is the parasitic contact resistance associated with the injection of charge carriers from the source electrode into the accumulation layer at the semiconductor-dielectric interface as well as the transport of the exiting charge carriers from the accumulation layer to the drain electrode. A finite contact resistance results in a fraction of the applied source-drain voltage dropping across the contacts and in a

corresponding reduction of the transistor current, and the linear field-effect mobility, respectively. This is particularly relevant in the so-called linear regime of the transistor where the source-drain voltage is small compared to the gate voltage. A suppression of the current in the linear regime significantly degrades the switching speed of the TFT. In an active matrix display application, for example, the linear operating regime of the transistor determines the switching speed, as the voltage difference between the signal on the data line, and the voltage on the pixel to be addressed approaches zero.

Several factors may contribute to the source and drain contact resistances.

- The conductivity of the conducting material that is in contact with the semiconducting polymer and forms the source and drain contacts.
- The existence of insulating layers on the surface of the source-drain contacts, such as unintentional oxide layers.
- At most metal-semiconductor interfaces a potential barrier exists. The shape of this potential barrier is determined by the difference between the Fermi energy of the metal and the ionisation potential (p-type semiconductor) and electron affinity (n-type), respectively, the image force experienced by a charge carrier in the semiconductor by image charges on the surface of the metal, as well as by the applied electric field. In normal operation of the TFT this so-called Schottky diode is reverse biased at the source, and forward biased at the drain.
- In a device configuration where the source-drain contacts are formed on the same side of the semiconducting layer as the accumulation layer (see Figure 1(a)) the Schottky potential barrier results in a short region between both the source and drain contacts and the accumulation layer in the channel in which no accumulation is possible, and in which the carrier concentration is low. In this region the current is ultimately limited by space-charge limited bulk conduction.

- In a device configuration where the source-drain contacts are formed on the opposite side of the accumulation layer (see Figure 1(b)) transport needs to occur through unaccumulated bulk of the semiconducting polymer layer. To minimize this contribution to the contact resistance the thickness of the semiconducting polymer film should be as small as possible.

In any particular device configuration several of the above factors might be contributing to the contact resistance, and the total parasitic contact resistance might be considered to be made of a series combination of the individual contact resistances associated with the different factors.

One of the techniques that has been applied successfully to minimize contact resistance in inorganic semiconductor devices such as amorphous silicon (a-Si) TFTs is the use of highly-doped p^+ and n^+ semiconductor contacts. In the so-called inverted-staggered (bottom-gate) configuration of an a-Si TFT, the intrinsic a-Si semiconducting layer is formed directly on top of the SiN dielectric layer. Then a highly doped n^+ a-Si layer is deposited followed by the deposition of a metal layer such as Cr. The Cr and n^+ a-Si layer are then patterned by photolithography and subsequent wet (Cr) and dry etching (n^+ a-Si). In this structure efficient electron injection into the intrinsic a-Si layer is from n^+ a-Si source/drain contacts with Cr interconnects. The use of a highly doped semiconducting contact of the same material from which the semiconducting channel is formed minimizes both the height of the potential barrier and the width of any carrier depleted region at the contacts, and results in efficient carrier injection.

For inorganic semiconductor devices formation of the highly doped p^+/n^+ contacts to the semiconductor is usually associated with additional processing steps such as deposition of a highly doped layer, ion implantation steps and additional

patterning steps. For polymer TFTs such processing steps are often difficult to perform, partly because of polymer degradation during ion implantation or solvent compatibility problems associated with photolithographic patterning. Furthermore, in general techniques to perform controlled doping with well-defined doping profiles are not established for polymer semiconductors.

In the current application we disclose a polymer transistor with highly doped p+/n+ source-drain contacts and controlled doping profiles, and methods for fabricating such source-drain contacts in such a way that the p+/n+ source-drain contacts are self-aligned with the metallic interconnects and electrodes of the device, and no additional patterning step is required.

Features and preferred features of the present invention are set out in the accompanying claims.

Preferably the conductivity of the organic semiconducting material is enhanced by doping throughout the interfacial layer. Most preferably the doping concentration throughout the interfacial layer is higher than 10^{17}cm^{-3} .

Preferably the interfacial layer is doped from the material of the conductive electrode adjacent the interfacial layer, most preferably by a component of that material.

There is suitably a layer of an organic semiconductor material in between the electrodes. The conductivity of the interfacial region is suitably enhanced relative to that of the remainder of the organic material and/or relative to its conductivity prior to doping.

The semiconductor layer preferably contacts both of the first and second electrodes. The semiconductor layer may comprise a plurality of semiconductor materials, which may be mixed or segregated.

The invention will now be described by way of example with reference to the following figures:

Figure 1 shows conventional bottom-gate (a) and top-gate (b) configurations for a polymer TFTs.

Figure 2 shows the process for fabricating a top-gate polymer TFT with highly doped source-drain contacts formed by depositing a solution of a semiconducting polymer onto a previously deposited pattern of a conducting polymer.

Figure 3 shows the process for fabricating a top-gate polymer TFT with highly doped source-drain contacts by depositing a solution of a semiconducting polymer onto a previously deposited pattern of an inorganic metal deposited from solution.

Figure 4 illustrates possible mechanisms for doping of a conjugated polymer in the presence of a polystyrene sulphonic acid counterion (A - protonation doping; B - doping by hole injection, C - direct doping).

Figure 5 shows a method for increasing the surface roughness of the conducting electrode by adding a surface active polymer or molecule to the ink of the conducting electrode, that can be redissolved selectively.

Figure 6 shows a method for forming a self-aligned layer of dopants on the surface of the electrode by mixing a surfactant into the ink of the conducting electrode.

Figure 7 shows a method for forming a layer of di-blockcopolymer on the surface of the electrode material, the blockcopolymer consisting of a conducting block A and a semiconducting block B.

In one embodiment of the present invention (Figure 2) a pattern of a conducting polymer 11 and 12 is first deposited onto the substrate. Deposition of the conducting polymer is preferably from solution. Examples for suitable deposition techniques are spin-coating, blade-coating or direct write techniques such as inkjet printing, offset printing or screen printing. The critical features of the conducting polymer pattern can be defined, for example, by photolithography or by solution deposition onto a high-resolution surface energy pattern 10 containing solution-repelling regions of low surface energy (PCT/GB00/04934). However, other patterning techniques might be used as well. The critical feature size between the conducting polymer patterns for source and drain 11 and 12 is preferably less than 20 μm . The conducting polymer can be in contact with an interconnect line 8,9 of an inorganic metal with a high conductivity, such as silver, copper, gold, tungsten, tantalum or indium tin oxide. The latter might be deposited and patterned by conventional vacuum deposition and photolithography although it is preferred if the inorganic metal is also deposited from solution, for example, using a nanoparticle dispersion or a chemical precursor. Deposition techniques such as inkjet printing, screen printing, electroless plating, laser forward transfer printing (UK 0116174.4) or other deposition and patterning techniques can be used. Inorganic metals can be solution deposited using, for example, from nanoparticle dispersions or chemical precursor solution. Usually, an annealing step is required in order to bring the as-deposited material into a high-conductivity state. In many applications of polymer TFTs a high conductivity metal to interconnect TFT devices or to connect the TFT devices/circuits to the outside world is required because conducting polymers have conductivities less than 1000 S/cm which is not sufficient for applications which require long interconnect lines and/or fast switching operation.

An alternative structure is shown in Figure 3. In this case the semiconducting polymer is in direct contact with the high conductivity interconnects/electrodes 8,9 without the intermediate conducting polymer electrode.

After depositing the conducting polymer pattern a solution of the semiconducting polymer 14, and 20, respectively, is deposited subsequently. Deposition techniques such as spin-coating, blade coating, dip coating, or direct write-techniques such as inkjet printing, screen printing, or offset printing may be used. After deposition of the semiconducting polymer the TFT device is completed by deposition of the gate dielectric layer 17 and the gate electrode 18. For the deposition of the gate electrode direct write techniques for conducting polymers or inorganic metals, such as inkjet printing, laser forward transfer printing, offset or screen printing may be used, as well as more conventional photolithography or other patterning techniques. The semiconducting layer might be either patterned into an active layer island (as in Figure 2 and 3) or it may be deposited as a continuous film over the substrate (as in Figure 5 to 7).

A conducting polymer consists of a conjugated polymer that is doped by mixing it with a counterion that is capable of either directly oxidizing (p-type) or reducing (n-type) the conjugated polymer or that is capable of stabilizing mobile charges on the chains of the conjugated polymer that have been generated during the synthesis of the conjugated polymer. The counterion can be a small molecular dopant or a polymeric dopant. Examples of polymeric dopants that are capable of oxidizing conjugated polymers such as polyethylenedioxythiophene (PEDOT) are poly(styrene sulfonic acid) (PSS), poly(ethylene-co-methacrylic acid) (PEMAA), or poly(acrylic acid) (PAA). In many cases a counterion with a relatively high molecular weight is desirable because a higher molecular weight reduces the tendency of the counterion to diffuse out of the conducting polymer layer into other layers of the device, which can give rise to undesirable changes of device

characteristics under long-time operation. It is known that at the direct interface between PEDOT/PSS and many semiconducting conjugated polymers the acidic PSSH groups result doping of the semiconducting polymer the is in direct contact with the PEDOT/PSS surface (Arias, Phys. Rev. B 60, 1854, 1999).

It has been shown by Sirringhaus et al. (Science 290, 2123 (2000)) that polymer TFTs fabricated with poly(dioctylfluorene-co-bithiophene) F8T2 and PEDOT/PSS source-drain electrodes exhibit a lower contact resistance than devices fabricated with gold source-drain electrode, although PEDOT has a slightly lower workfunction than gold. This observation is interpreted as being due to the formation of a doped interfacial layer at the PEDOT/PSS – F8T2 interface. However, in the case of PEDOT doped with a polymeric counterion of PSS this interfacial region is very narrow, since the PSS polymeric counterion cannot diffuse into the semiconducting layer, i.e. doping just occurs in the region where the semiconducting polymer is in direct contact with the PEDOT/PSS.

The subject of the present application is to disclose techniques by which such naturally occurring doping can be enhanced and an interfacial region 15 and 16 of finite thickness (Figure 2) of the semiconducting polymer around the conducting polymer electrodes 11 and 12, respectively, is formed, that is highly doped. These self-aligned, highly doped regions 15 and 16 then act as highly efficient injecting source and drain contacts into the intrinsic semiconducting polymer in the channel of the TFT.

According to a first aspect of the present invention a method is disclosed by which a highly doped interfacial layer is formed when the semiconducting polymer is deposited on top of a metallic interconnect that contains a dopant molecule that is able to diffuse out of the metallic interconnect into the semiconducting polymer.

In one embodiment of the invention an oligomeric dopant molecule is added to a conducting polymer ink formulation such as PEDOT/PSS that form the source-drain interconnects. In the case of PEDOT/PSS a suitable dopant molecule is an oligomer of PSS, that is sufficiently short, that it is able to diffuse into the semiconducting layer.

Without wanting to be bound by theory possible mechanism for this doping mechanisms are illustrated in Figure 4. In Figure 4A the doping mechanism is chemical doping, that occurs by protonation. In Figure 4B, the doping occurs during operation of the device when hole carriers are injected into the device from the electrodes, and are stabilized on the polymer chain by the favourable electrostatic interaction with the negative counterions on the PSS. In Figure 4C doping occurs by direct oxidation of the polymer by the acidic negative SO_3^- functional groups of the PSS.

We have also found that in double layer structures in which a semiconducting layer is deposited on top of a layer of PSS a significant increase of the conductivity of the F8T2 occurs. In these experiments the PSS was annealed at a temperature of 200°C prior to deposition of the F8T2 in order to minimize any ionic current flow in the PSS. While reference films fabricated with pure F8T2 as well as pure PSS showed very low conductivity, the F8T2/PSS bilayer films showed significant level of conductivity, indicative of doping at the PSS/F8T2 interface. These experiments yield evidence that even the direct doping reaction (Figure 4C) of F8T2 in the presence of PSS might occur.

According to the preferred aspects of the present invention, a significant improvement of the contact resistance can be achieved by mixing a counterion dopant into the conducting polymer ink that is able to diffuse into the semiconducting polymer forming a highly doped interfacial region with a finite thickness exceeding 1nm. In one embodiment of the invention the diffusion of the

dopant can be induced during an annealing step at elevated temperature of typically 50-300 °C after the deposition of the semiconducting polymer. In order to enhance the mobility of the dopant such annealing step can also be performed under a solvent atmosphere. The diffusion profile can be controlled with the molecular weight of the dopant molecule. The lower the molecular weight of the dopant the deeper the diffusion profile. In many cases there is a compromise between efficient source-drain injection, and other performance attributes of the device such as low OFF current, and device stability. In one embodiment of the invention the counterion is an oligomer of styrene sulphonic acid, ethylene-co-methacrylic acid or acrylic acid. The number n of monomer units of the oligomer can be chosen such as to achieve the desired diffusion profile at the annealing temperature at which the diffusion is driven. N should be sufficiently large that under typical operating conditions of the device no further significant diffusion occurs, and that the width of the doped region surrounding the conducting polymer electrodes is small compared to the channel length, i.e. typically less than 10% of the distance between the two conducting polymer electrodes.

An alternative method to drive the diffusion of the dopants into the semiconducting layer is to apply a current stress to the device, such that positive (negative) charge carriers are injected into the device from the source-drain electrodes. The presence of a space charge of injected carriers near the electrodes will enhance the diffusion of negatively (positively) charged dopants out of the electrodes, as the electrostatic repulsion that they would otherwise experience can be compensated for by the presence of the oppositely charged injected carriers.

An alternative method to induce the diffusion is to deposit the semiconducting polymer from a solution in a solvent or a mixture of solvents in which the dopant has a small, but finite solubility, such that during the deposition of the semiconducting polymer dopant molecules near the surface of the conducting polymer electrodes are dissolved into the solution of the semiconducting polymer

and diffuse into the semiconducting polymer. In this case the diffusion profile can be controlled with the solubility of the dopant molecules in the solvent of the semiconductor ink. The solubility should be sufficiently small that the dopant molecules are not uniformly distributed in the solution of the semiconducting polymer. The dissolution rate should be sufficiently small that dissolution effectively occurs in the later stages of film growth where the characteristic time constant for diffusion of dopants in the concentrated semiconductor solution is smaller than the time constant associated with the drying of the film.

Examples of such dopants are molecules containing both polar and apolar side chains. The requirement is that the dopant molecule is soluble both in a solvent that is miscible with the solvent that is used for the deposition of the conducting polymer, and in a solvent that is miscible with the solvent that is used for the deposition of the semiconducting polymer. Alternatively, the codeposition of the conducting polymer and the dopant molecule can be performed using surfactant additives to the conducting polymer ink. The aliphatic tails of the surfactant stabilize, for example, a nonpolar dopant molecule inside a polar solution of the conducting polymer such as a water solution of PEDOT/PSS.

The methods described above can also be applied in order to enhance the injection into the semiconducting material from inorganic electrodes solution-deposited using nanoparticle or chemical precursor inks.

According to a second aspect of the present invention a method is disclosed by which the source-drain injection efficiency is improved by modification of the surface roughness of the electrode to promote interfacial contact between the metallic electrode and the semiconducting layer. In contact with a microporous electrode the interfacial area that is available for charge injection into the semiconducting polymer can be increased significantly. This is particularly important in device configuration in which the source-drain electrodes and the

accumulation layer are on the same side of the semiconducting polymer film, because in such configurations the injected current flow is confined to a very thin layer at the interface between the electrodes and the gate dielectric. Furthermore in the case of an electrode at which there is a doping interaction between the semiconducting polymer and the material of the conducting electrode, such as in the case of PEDOT/PSS, the larger the interfacial contact area is the more efficient the doping of the semiconducting polymer in contact with PSS.

The surface roughness of the electrodes can be enhanced prior to deposition of the semiconducting material by a variety of techniques such as oxygen plasma etching or mechanical treatment of the electrodes such as mechanical rubbing. In one preferred embodiment of the invention a polymer additive is mixed into the solution of the conducting material (see Figure 5). The polymer additive is chosen such that upon drying it forms a phase separated network with the conducting material 22,23. The polymer might also have a tendency to phase separate vertically. An example of such a polymer additive is polyvinylphenol (PVP) that can be codeposited with PEDOT/PSS from a solvent mixture of water and isopropanol. A suitable concentration of PVP:PEDOT/PSS is 10%. Prior to deposition of the semiconducting polymer the polymer additive near the surface of the electrode is redissolved by exposing the surface of the electrodes to a solvent in which the conducting material is not soluble, but in which the polymer additive is soluble, such as isopropanol in the case of dried PEDOT/PSS. In this way a microporous surface 24 is formed. The porosity, and the depth of the porous layer can be controlled with the original phase separated microstructure (that can for example be controlled by annealing treatment or suitable choice of solvents), by the time and temperature conditions of the solvent exposure step, or by the choice of the solvent. When a semiconducting polymer is deposited subsequently onto such a microporous electrode, it penetrates into the pores on the surface and comes into intimate contact with the conducting electrode material resulting in enlarged interface area as well as doping efficiency.

It should be pointed out, however, that the micro-roughness of the electrode needs to be sufficiently small that other device performance attributes such as leakage currents through the dielectric layer or the uniformity of film deposition of the semiconducting material are not adversely affected.

According to another aspect of the present invention a small concentration of semiconducting polymer is added to the ink of the conducting material, either by directly dissolving the semiconducting material in the conducting ink solvent, or by mixing in a cosolvent miscible with the solvent of the conducting ink, or by dispersing the semiconducting material inside the conducting polymer ink using a surfactant. When the ink dries after deposition, the semiconducting polymer has a tendency to segregate to the surface (due to its less polar nature), and near the surface a mixed layer of conducting and semiconducting material is formed in which effective doping of the semiconducting material occurs. The semiconducting polymer maybe the same polymer that is used as the active layer of the device, or it may be a different polymer.

According to yet another aspect of the invention a method is disclosed by which a self-aligned layer of dopants and/or layer of defined surface charge is formed by mixing the ink of the conducting electrode material with a surface active molecule, or by selectively modifying the surface after deposition of the conducting electrodes.

In one embodiment of this aspect of the invention (Figure 6) the ink of the metallic electrode material 27 is mixed with a surfactant dopant or with a dopant molecule that is stabilized within the conducting ink with the help of a surfactant. A surfactant dopant is a molecule that comprises both a polar head group as well as a non-polar aliphatic or fluorinated tail group. The polar head group can provide the dopant functionality directly, or the dopant functionality can also be

incorporated by attaching a functional group to the surfactant that is capable of oxidizing or reducing the semiconducting polymer. The surfactant molecule is surface active and migrates to the surface in order to expose its aliphatic tails to the surface and lower the surface energy. In this way a self-aligned surface layer of dopant molecules 28 is formed on the surface of the electrodes 26, 27.

In the case of PEDOT/PSS and p-type doping of the semiconductor a suitable surfactant dopant is an anionic surfactant that contains a negatively charged sulphonic acid head group, and an alkyl or fluoroalkyl side chain. In the case of n-doping a preferred embodiment of the invention is a cationic surfactant that contains a positively charged head group, and an alkyl or fluoroalkyl side chain. Suitable surfactants are known in the literature. The concentration of the surfactant in the conducting ink should be chosen in order to maximise the surface activity of the surfactant and minimize any interactions of the surfactant with the conducting material, that might deteriorate the conducting properties. In one preferred embodiment of the invention the concentration of the surfactant is chosen to be near the critical micelle concentration.

The molecular weight of the surfactant should be chosen in order to maximise the surface activity, while at the same time ensuring that the thin layer of nonpolar, insulating tails of the surfactant does not affect adversely the charge injection. The molecular weight should be high enough in order to prevent uncontrolled diffusion of the surfactant into the other layers of the device. In one preferred embodiment of the invention the surfactant is a polymeric surfactant.

In another embodiment of the invention the surfactant is a surfactant that is not a direct dopant, but a surfactant that has a permanent dipole moment, such as an amphoteric surfactant, or (in the case of hole injection) a cationic surfactant with a strongly electronegative tail group such as a fluorinated tail group. On a negatively charged PSS-rich PEDOT/PSS surface the positive head groups of the surfactant

are directed towards the surface such that the dipole moment of the surfactant is helping the hole injection process.

In contrast to the familiar modification of metal surface by exposure of the surface to thiol-based self-assembling molecules the surfactant layer forms automatically during the deposition process of the conducting electrode, and is self-aligned with the conducting electrode. The interaction of the surfactant with the polymer surfaces is of an ionic origin, and provides a means for achieving a densely packed surface layer of surfactants in contrast to thiol or trichlorosilane based self-assembling molecules that require specific functional groups on the surface for binding, and on polymer surfaces usually do not grow into densely packed layers.

In an alternative embodiment of this aspect of the invention the surface layer of dopants or dipolar surfactants is deposited selectively onto the surface of predeposited conducting electrodes. Selective deposition implies that the dopant deposits only on top of the conducting electrodes, but not on top of the bare substrate surface, in particular not in the channel of the TFT.

In one embodiment selective deposition is achieved by depositing an ionic dopant from solution or from the vapour phase onto the charged surface of a conducting polymer electrode while the bare substrate surface is either uncharged or charged with the same polarity as that of the ionic dopant/surfactant. The substrate surface can be modified accordingly by deposition of a self-assembled monolayer prior to the deposition of the conducting electrode. This ensures that deposition of the dopant is selective and only occurs on top of the conducting electrode. The conducting polymer PEDOT/PSS consists of a blend of a positively charged conjugated polymer (PEDOT) and a negatively charged counterion (PSS). This results in a surface that exposes a large number of charged groups that can be used to bind the dopant molecules by electrostatic interaction. The PSS

component has a tendency to surface segregate, resulting in a negatively charged surface, in particular after annealing of an as-deposited PEDOT/PSS film at temperatures exceeding 150°C.

One of the techniques that can be used to self-assemble a surface layer of dopants onto an electrode of PEDOT/PSS is that of polyelectrolyte self-assembly [Decher, Science 277, 1232 (1997)]. Polyelectrolyte self-assembly has been used previously to improve the charge injection into a polymer light-emitting diode by building a graded injection multilayer structure with a sequence of polymer of increasing energy gap in order to reduce the injection barriers from the anode into the hole transport layer (Ho, Nature 404, 481 (2000)). Here we disclose a technique by which a self-assembled doped layer can be formed using polyelectrolyte self-assembly. The PEDOT/PSS is prepared with a well-defined surface charge, either by inducing the segregation of either the PSS or the PEDOT component to the surface or by treating the surface with a self-assembled monolayer comprising a charged tail group. Such a charged surface is then dipped into a polyelectrolyte solution comprising an ionic polymer with charged groups that bind to the charged groups on the PEDOT/PSS surface. This process can be used to build multilayer structures consisting of alternating layer of polyanions and polycations. The polyanions and polycations are chosen such that they exhibit conducting or semiconducting properties in order not to result in a barriers for charge transport. One or more of the polyanion or polycation layers, most preferably the outermost layer, comprises functional groups that are able to oxidize/reduce the semiconducting polymer. In the case of PEDOT/PSS such functional group can be a group of styrene sulphonic acid, and the polyanion may be PSS itself.

According to yet another aspect of the invention a device is disclosed in which the injection efficiency is enhanced by assembling a layer of a conducting-

semiconducting blockcopolymer on the surface of the metallic interconnect prior to deposition of the semiconducting layer.

The di-blockcopolymer consists of a first conducting or at least easily oxidizable (reducible) block A with a low ionisation potential (high electron affinity, respectively), and of a semiconducting block B with a high ionisation potential (low electron affinity) (Figure 7). In a preferred embodiment of the invention the semiconducting block is of the same chemical structure as the semiconducting polymer that forms the active layer of the TFT. The semiconducting block may for example be an oligomer or polymer of regioregular hexylthiophene or dioctylfluorene-co-bithiophene. The conducting block maybe an oligomer of ethylenedioxythiophene.

The blockcopolymer is assembled in a lamellar structure onto the surface of the conducting electrodes in such a way that the conducting block A is directed towards the bulk of the conducting electrode, and the semiconducting block B is in contact with the semiconducting layer.

Without wanting to be bound by theory the mechanism for the improved injection in this case is believed to be the existence of a covalent bond and the generally close contact between the conducting and semiconducting block, that will facilitate doping and/or charge injection from the conducting into the semiconducting material.

In one embodiment of this aspect of the invention the lamellar structure can be fabricated by mixing the blockcopolymer into the conducting ink and inducing a vertically phase separated structure upon drying with the apolar semiconducting block of the blockcopolymer segregated to the surface. The apolar nature of the semiconducting block and the more polar nature of the conducting block will favour such vertically phase separated in which the surface energy is lowered by

exposing the apolar semiconducting block to the surface. In another embodiment of the invention the lamellar surface layer of the blockcopolymer is deposited selectively after the deposition of the conducting electrodes by techniques analogous to those described above, by making use of the binding of the polar block to the surface of the conducting electrode.

In a preferred embodiment the blockcopolymer is a di-blockcopolymer. However, tri-blockcopolymers or higher blockcopolymers may also be used.

The methods for improving carrier injection into organic semiconductors disclosed in this invention can be used for the fabrication of high performance TFT, as well as TFT circuits such as logic circuits, sensor circuits, and active matrix displays. They may also be used in other organic electronic devices which require efficient electron and hole injection such as light-emitting diodes, or rectifying diodes.

The techniques can also be applied to devices in which the semiconducting material is an inorganic semiconductor deposited from solution, such as silicon or CdSe deposited using chemical precursor solutions or nanocrystal dispersions.

The present invention is not limited to the foregoing examples. Aspects of the present invention include all novel and/or inventive aspects of the concepts described herein and all novel and/or inventive combinations of the features described herein.

The applicant draws attention to the fact that the present inventions may include any feature or combination of features disclosed herein either implicitly or explicitly or any generalisation thereof, without limitation to the scope of any definitions set out above. In view of the foregoing description it will be evident to a person skilled in the art that various modifications may be made within the scope of the inventions.

CLAIMS

1. An electronic device comprising a substrate, a first conducting electrode, a second conducting electrode spaced away from the first conducting electrode, a layer of an organic semiconductor material in between the first and second conducting electrodes, the organic semiconductor material comprising an interfacial region at its interface with at least one of the first or second electrode in which the conductivity of the organic semiconducting material is enhanced by doping.
2. An electronic device as claimed in claim 1 in which the thickness of said interfacial layer is larger than 1nm.
3. An electronic device as claimed in claim 1 and 2, in which the doping concentration in said interfacial layer is higher than 10^{17}cm^{-3} .
4. An electronic device comprising a substrate, a first conducting electrode, a second conducting electrode spaced away from the first conducting electrode, a layer of an organic semiconductor material in between the first and second conducting electrodes, the organic semiconductor material comprising an interfacial region at its interface with at least one of the first or second electrode, and said organic semiconductor material comprising a blockcopolymer with a conducting block and a semiconducting block.
5. An electronic device as claimed in any preceding claim in which at least one of said first or second electrodes comprises a conducting polymer.
6. An electronic device as claimed in claim 5 in which said conducting polymer is PEDOT/PSS.
7. An electronic device as claimed in any of claims 1 to 4, in which at least one of said first or second electrodes comprises an inorganic metal that is deposited from a solution.
8. An electronic device as claimed in claim 7, in which said inorganic metal is silver, gold, or copper.

9. An electronic device as claimed in any preceding claim in which the first and second electrodes form source and drain electrodes of an electronic switching device.
10. A method for forming an electronic device comprising a substrate, a first conducting electrode, a second conducting electrode spaced away from the second conducting electrode, a layer of an organic semiconductor material in between the first and second conducting electrode, the organic semiconductor material comprising an interfacial region at its interface with at least one of the first or second electrode in which the conductivity of the organic semiconducting material is enhanced by doping, the method comprising depositing at least one of the first or second electrodes from a solution including a dopant for said organic semiconductor that is able to diffuse into the organic semiconducting layer to form the said region.
11. A method as claimed in claim 10, comprising the step of annealing the substrate after the deposition of both the first or second electrode and the layer of organic semiconductor.
12. A method as claimed in claim 10 or 11, wherein said dopant is an oligomer of an organic molecule comprising an acid functional group.
13. A method as claimed in claim 12, wherein said oligomer is an oligomer of an organic molecule containing a sulphonic acid group.
14. A method for forming an electronic device comprising a substrate, a first conducting electrode, a second conducting electrode spaced away from the second conducting electrode, a layer of an organic semiconductor material in between the first and second conducting electrode, the organic semiconductor material comprising an interfacial region at its interface with at least one of the first or second electrode and said layer of organic semiconductor in which the conductivity of the organic semiconducting material is enhanced by doping, the method comprising forming at least one of the first or second conducting electrode, increasing roughening the

surface of the said at least one of the first or second conducting electrode, and subsequently depositing the layer of organic semiconductor material.

15. A method as claimed in claim 14, comprising the step of depositing at least one of the first or second electrodes from a solution including a conducting material and a polymer, and exposing the surface of the substrate after deposition of the first or second electrode to a solvent in which said polymer is soluble, wherein the conducting material forms the said at least one of the first or second electrodes.
16. A method for forming an electronic device comprising a substrate, a first conducting electrode, a second conducting electrode spaced away from the second conducting electrode, a layer of an organic semiconductor material in between the first and second conducting electrode, the organic semiconductor material comprising an interfacial region at its interface with at least one of the first or second electrode in which the conductivity of the organic semiconducting material is enhanced by doping, the method comprising the step of depositing at least one of the first or second electrodes from a solution that contains a surface active dopant.
17. A method for forming an electronic device as claimed in claim 16, in which said surface active dopant is a surfactant.
18. A method for forming an electronic device comprising a substrate, a first conducting electrode, a second conducting electrode spaced away from the second conducting electrode, a layer of an organic semiconductor material in between the first and second conducting electrode, the organic semiconductor material comprising an interfacial region layer at its interface with at least one of the first or second electrode in which the conductivity of the organic semiconducting material is enhanced by doping, the method comprising the step of depositing at least one of the first or second electrodes from a solution that contains molecules of said organic semiconductor.

19. A method for forming an electronic device comprising a substrate, a first conducting electrode, a second conducting electrode spaced away from the first conducting electrode, a layer of an organic semiconductor material in between the first and second conducting electrode, the organic semiconductor material comprising an interfacial layer at its interface with at least one of the first or second electrode in which the conductivity of the organic semiconductor material is enhanced by doping, the method comprising the step of depositing at least one of the first or second electrodes from a solution that contains a blockcopolymer with a conducting block and a semiconducting block.
20. A method for forming an electronic device comprising a substrate, a first conducting electrode, a second conducting electrode spaced away from the first conducting electrode, a layer of an organic semiconductor material in between the first and second conducting electrode, the organic semiconductor material comprising an interfacial region at its interface with at least one of the first or second electrode in which the conductivity of the organic semiconducting material is enhanced by doping, the method comprising depositing a layer of dopant molecules onto the surface of at least one of said first or second electrodes.
21. A method as claimed in claim 20 wherein said layer of dopant molecules is deposited by polyelectrolyte self-assembly.
22. A method as claimed in any of claims 10 to 21 wherein at least one of said first or second electrodes comprises a conducting polymer.
23. A method as claimed in any of claims 10 to 21 wherein at least one of said first or second electrodes comprises an inorganic metal that is deposited from solution.
24. A method as claimed in any of claims 10 to 21, wherein said layer of organic semiconductor is a conjugated polymer.
25. A method as claimed in claim 24, wherein the ionisation potential of said conjugated polymer is less than 5.8eV.

26. A method for forming an electronic device comprising a substrate, a first conducting electrode, a second conducting electrode spaced away from the first conducting electrode, a layer of an organic semiconductor material in between the first and second conducting electrode, the method comprising doping the organic semiconductor material at its interface with at least one of the first or second electrode to form an interfacial region at that interface in which the conductivity of the organic semiconducting material is enhanced.
27. A method as claimed in claim 26, where the organic semiconductor material is doped by a component of the said one of the first or second electrodes.

ABSTRACT**Self-aligned doping of source-drain contacts**

A method for forming an electronic device comprising a substrate, a first conducting electrode, a second conducting electrode spaced away from the first conducting electrode, a layer of an organic semiconductor material between the first and second conducting electrode, the organic semiconductor material comprising an interfacial region at its interface with at least one of the first or second electrode in which the conductivity of the organic semiconducting material is enhanced by doping, the method comprising depositing at least one of the first or second electrodes from a solution including a dopant for said organic semiconductor that is able to diffuse into the organic semiconducting layer to form the said region.

Figure 2

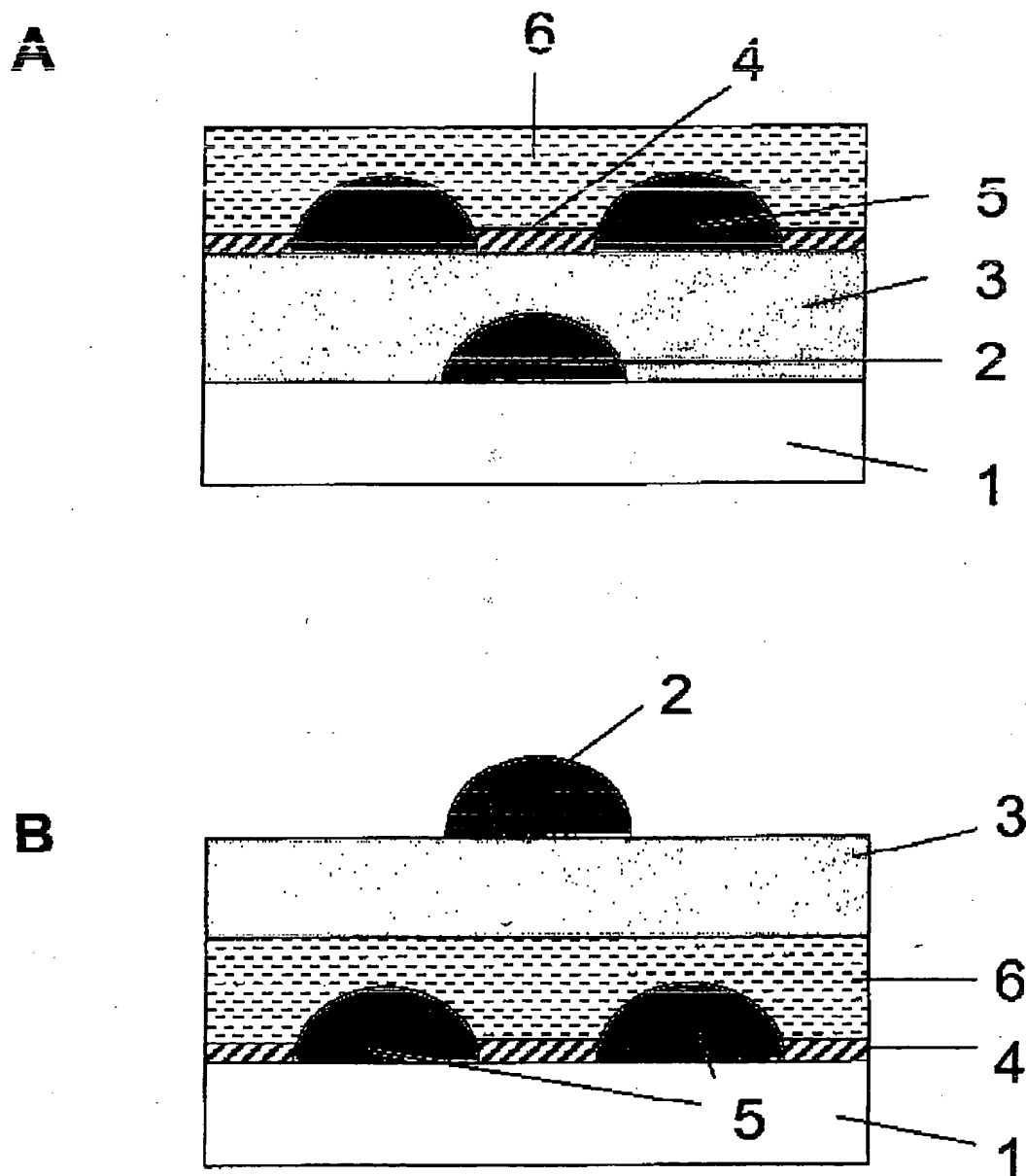


Fig. 1

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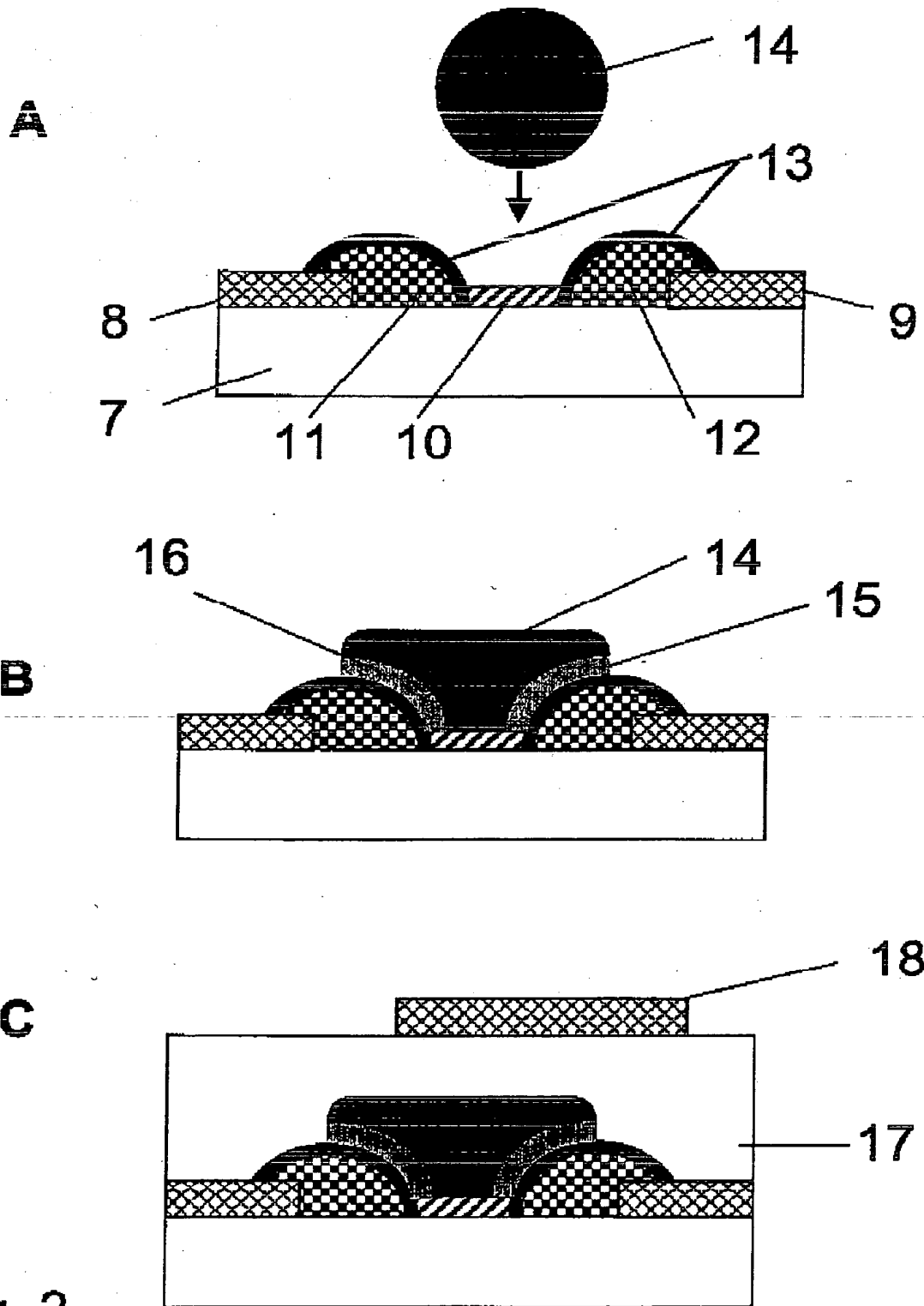


Fig. 2

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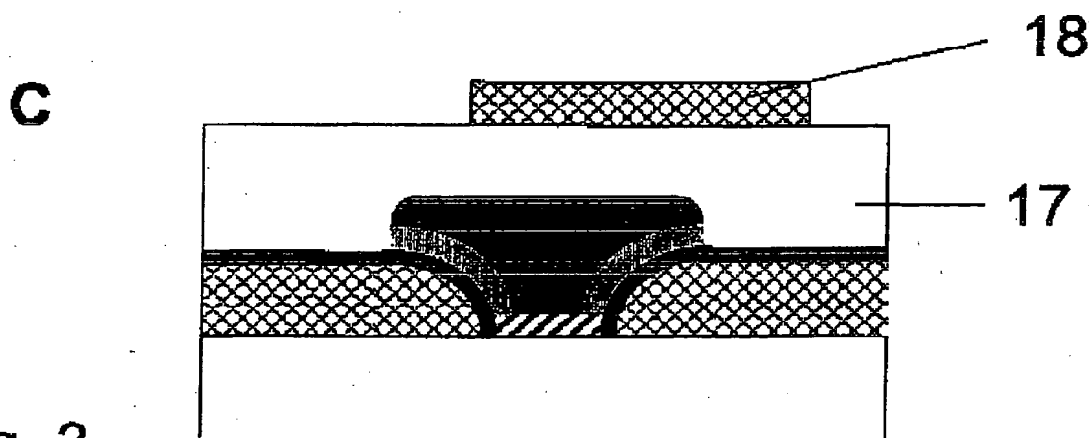
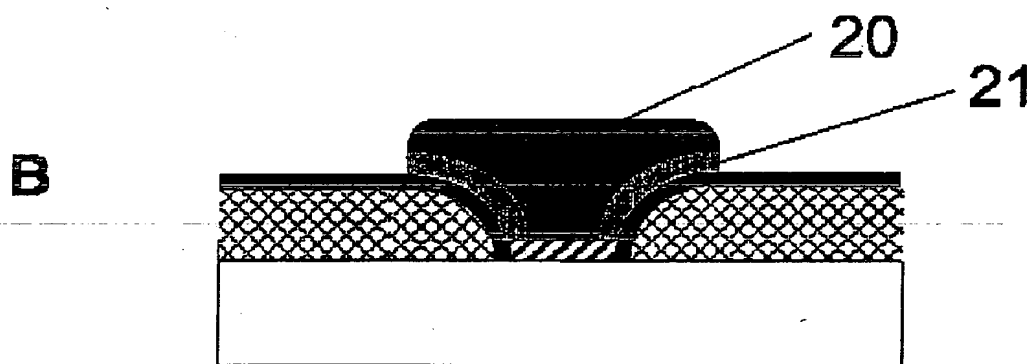
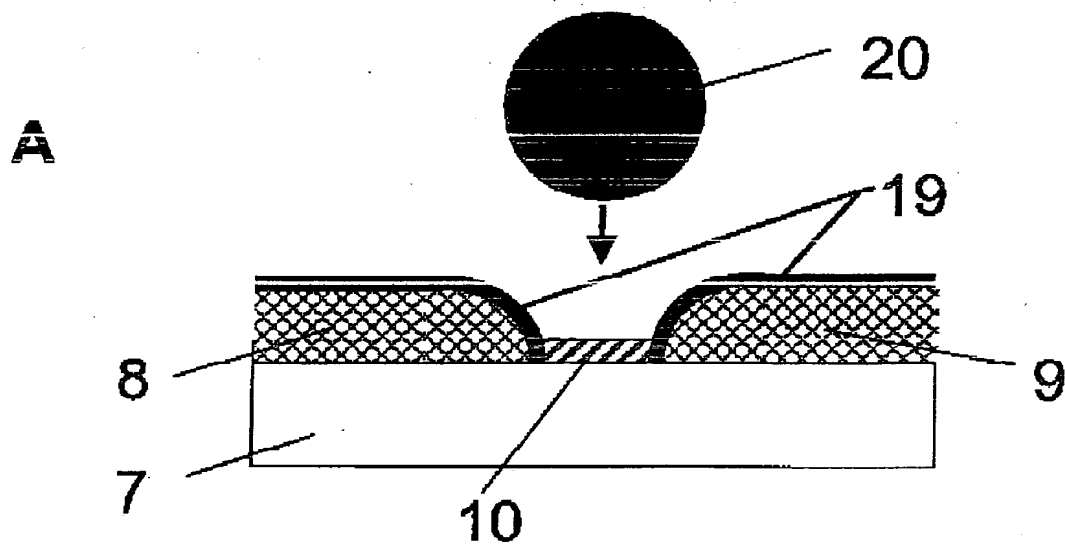
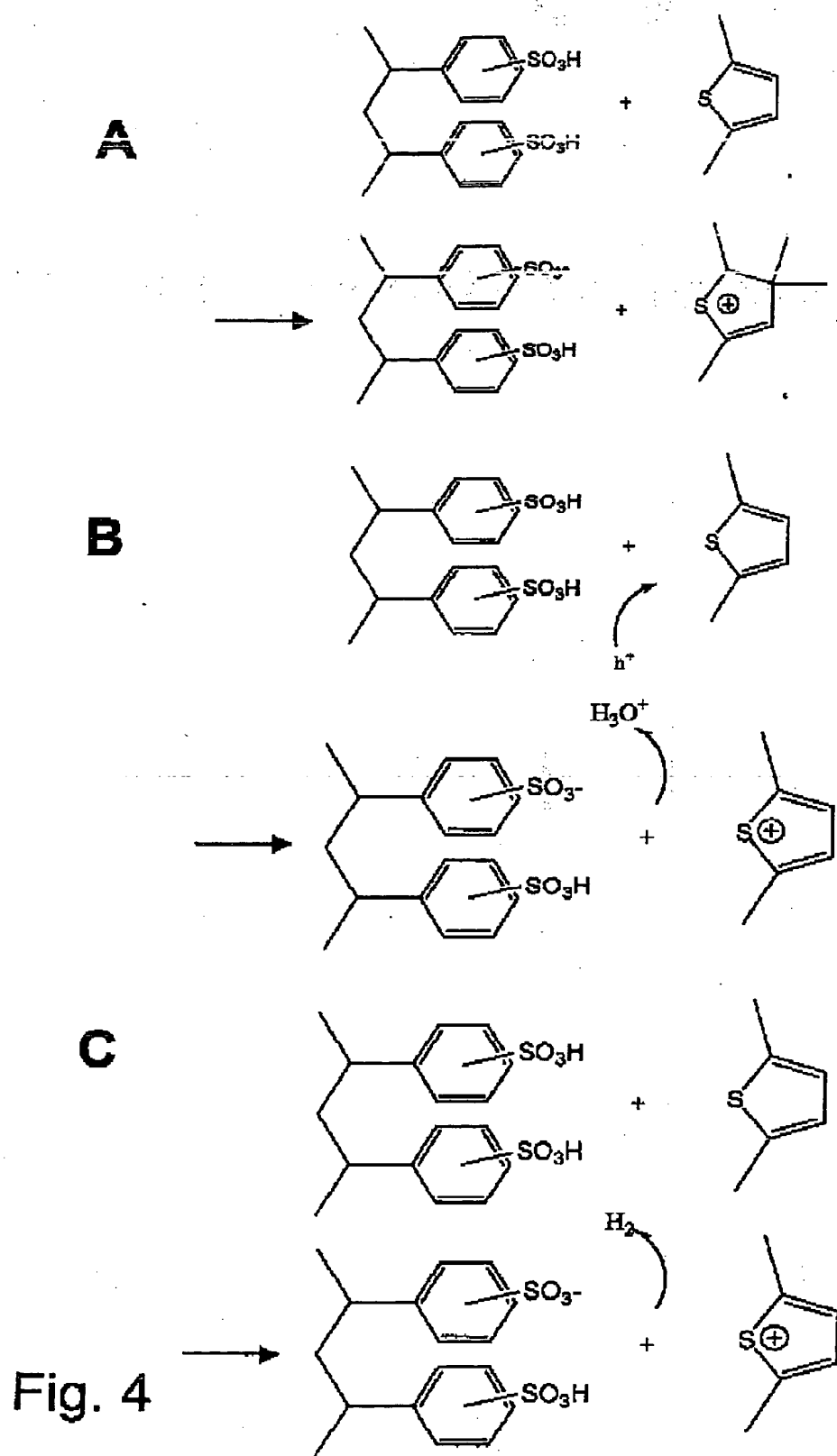


Fig. 3

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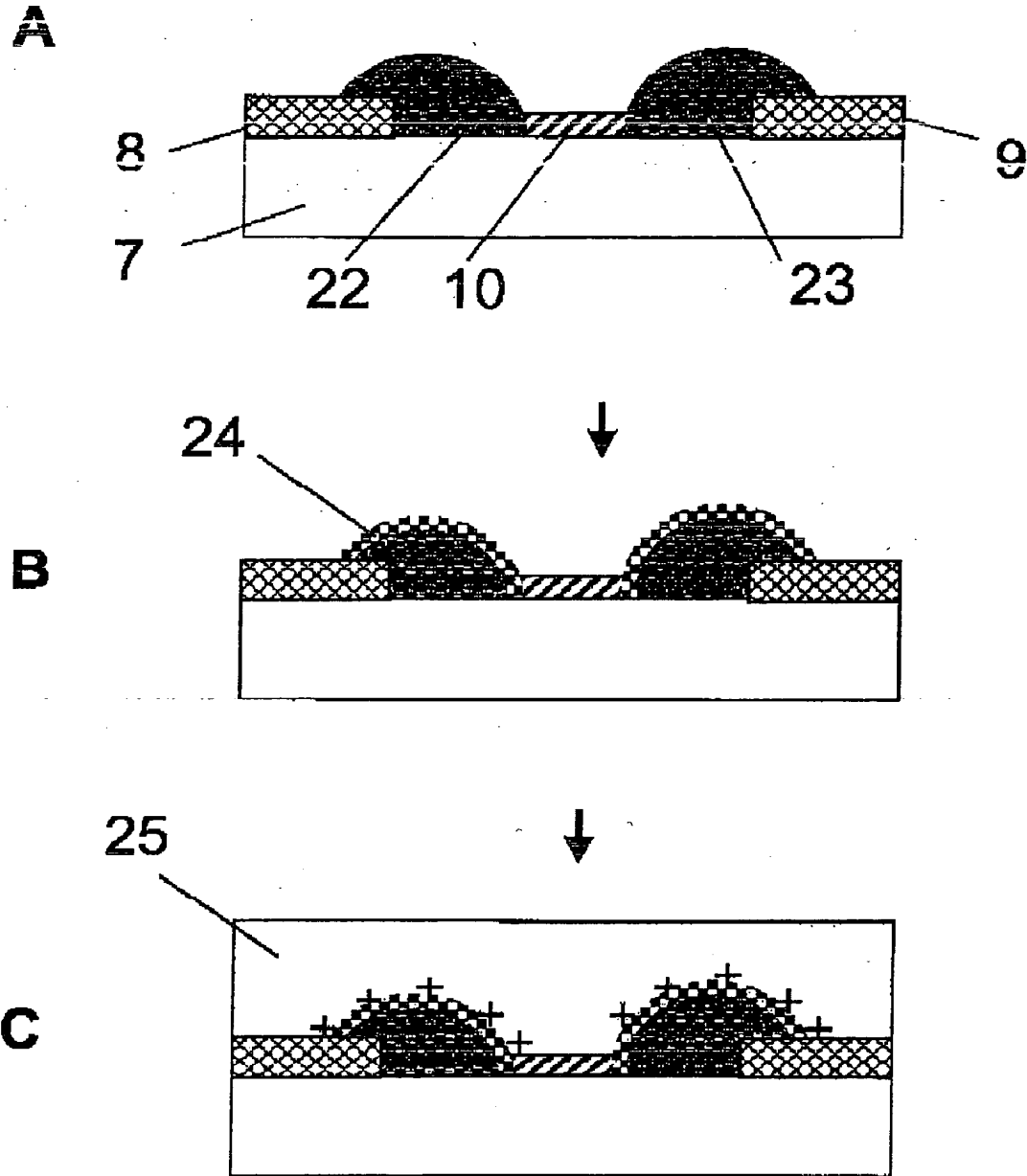


Fig. 5

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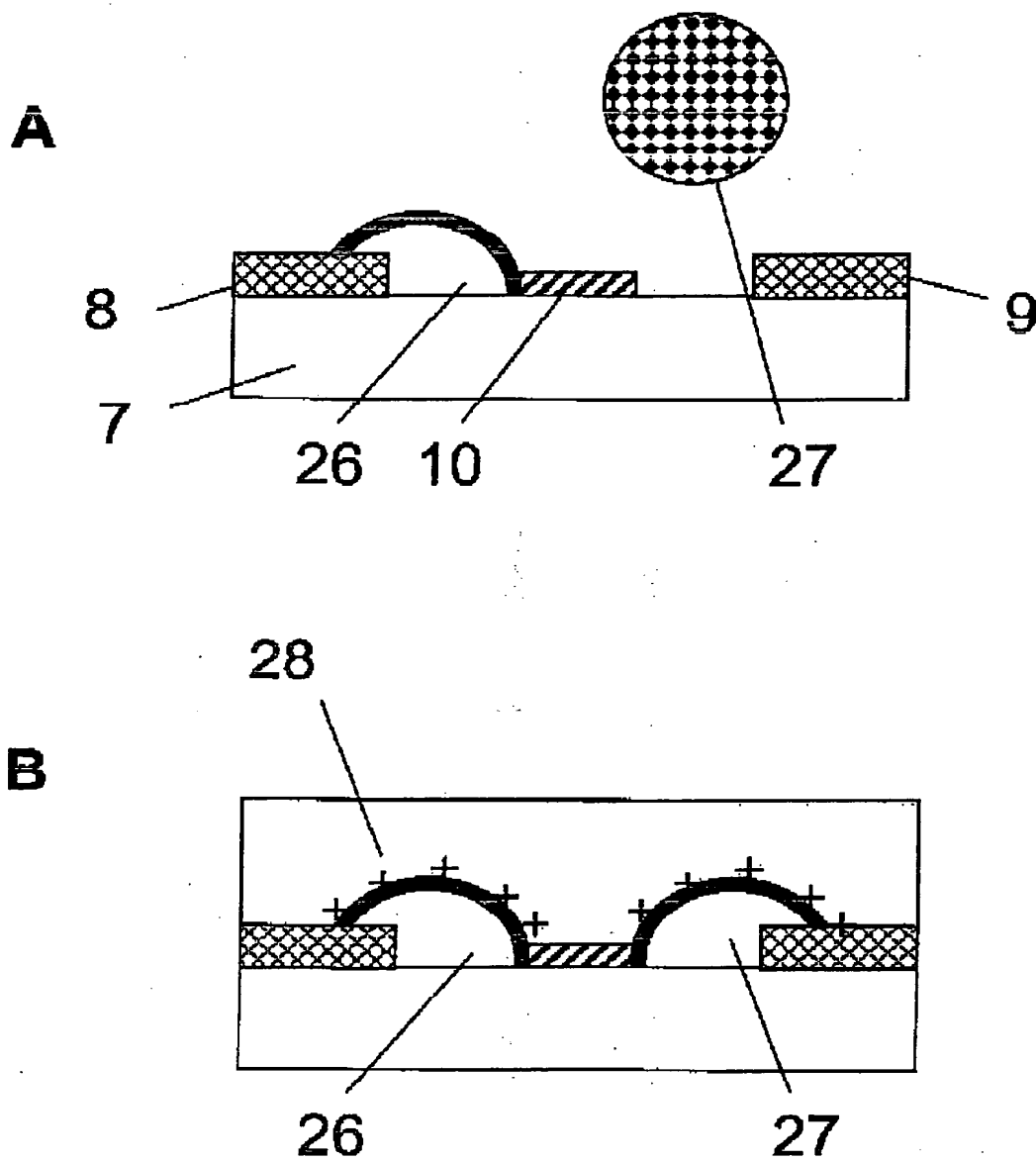


Fig. 6

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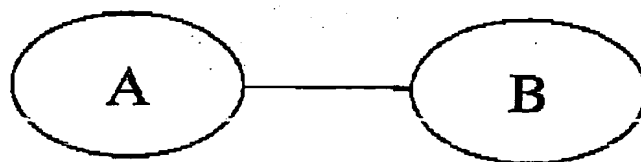
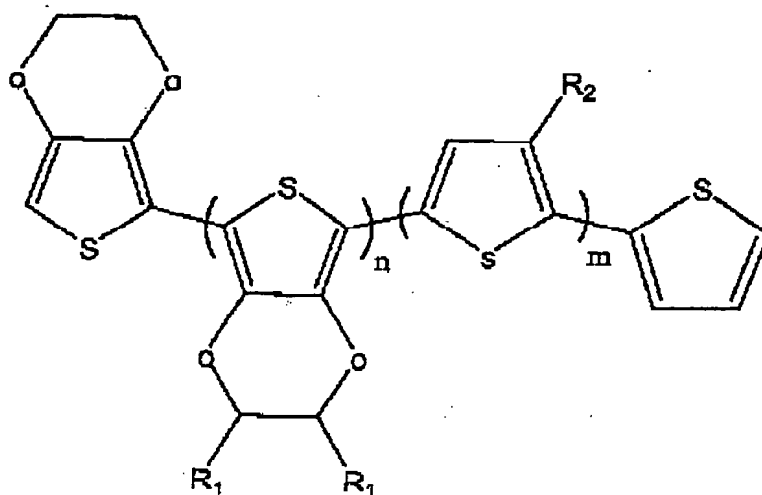
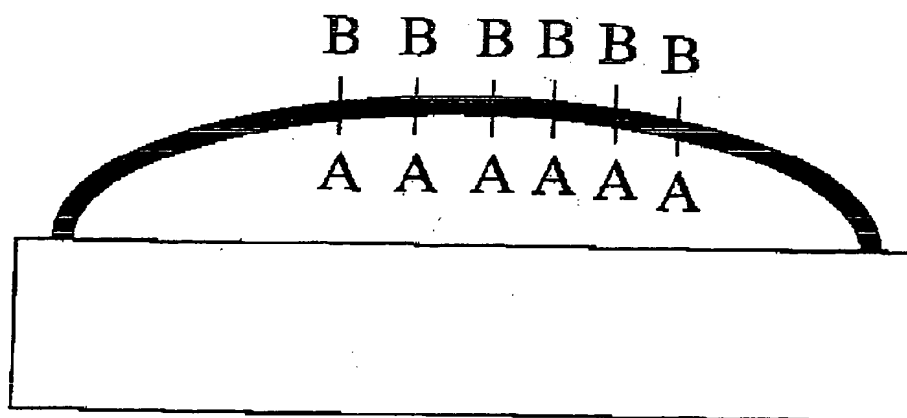
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Fig. 7

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